

L Number	Hits	Search Text	DB	Time stamp
1	619305	gate\$1	USPAT; US-PGPUB; JPO	2004/11/06 17:23
2	168155	implant\$3	USPAT; US-PGPUB; JPO	2004/11/06 17:24
3	16092	ldd or (lightly adj doped adj (region\$1 or drain\$1))	USPAT; US-PGPUB; JPO	2004/11/06 17:24
4	264404	spacer\$1	USPAT; US-PGPUB; JPO	2004/11/06 17:24
5	9248	second adj2 spacer\$1	USPAT; US-PGPUB; JPO	2004/11/06 17:25
6	8982	first adj2 spacer\$1	USPAT; US-PGPUB; JPO	2004/11/06 17:25
7	171466	source same drain	USPAT; US-PGPUB; JPO	2004/11/06 17:25
8	5587	gate\$1 same (ldd or (lightly adj doped adj (region\$1 or drain\$1))) same implant\$3	USPAT; US-PGPUB; JPO	2004/11/06 17:26
9	5373	(second adj2 spacer\$1) same (first adj2 spacer\$1)	USPAT; US-PGPUB; JPO	2004/11/06 17:26
10	381	(source same drain) and (gate\$1 same (ldd or (lightly adj doped adj (region\$1 or drain\$1))) same implant\$3) and ((second adj2 spacer\$1) same (first adj2 spacer\$1))	USPAT; US-PGPUB; JPO	2004/11/06 17:26
11	165795	(silicon adj nitride) or sin or si3n4 or "si.sub.3 n.sub.4"	USPAT; US-PGPUB; JPO	2004/11/06 17:27
12	261631	(silicon adj (oxide or dioxide)) or sio2 or "sio.sub.2"	USPAT; US-PGPUB; JPO	2004/11/06 17:27
13	9360	((silicon adj nitride) or sin or si3n4 or "si.sub.3 n.sub.4") same spacer\$1	USPAT; US-PGPUB; JPO	2004/11/06 17:27
14	11696	((silicon adj (oxide or dioxide)) or sio2 or "sio.sub.2") same spacer\$1	USPAT; US-PGPUB; JPO	2004/11/06 17:27
15	6298	((silicon adj nitride) or sin or si3n4 or "si.sub.3 n.sub.4") same spacer\$1 and (((silicon adj (oxide or dioxide)) or sio2 or "sio.sub.2") same spacer\$1)	USPAT; US-PGPUB; JPO	2004/11/06 17:27
16	182	((source same drain) and (gate\$1 same (ldd or (lightly adj doped adj (region\$1 or drain\$1))) same implant\$3) and ((second adj2 spacer\$1) same (first adj2 spacer\$1))) and (((silicon adj nitride) or sin or si3n4 or "si.sub.3 n.sub.4") same spacer\$1) and (((silicon adj (oxide or dioxide)) or sio2 or "sio.sub.2") same spacer\$1)	USPAT; US-PGPUB; JPO	2004/11/06 17:28
17	199	((source same drain) and (gate\$1 same (ldd or (lightly adj doped adj (region\$1 or drain\$1))) same implant\$3) and ((second adj2 spacer\$1) same (first adj2 spacer\$1))) not (((source same drain) and (gate\$1 same (ldd or (lightly adj doped adj (region\$1 or drain\$1))) same implant\$3) and ((second adj2 spacer\$1) same (first adj2 spacer\$1))) and (((silicon adj nitride) or sin or si3n4 or "si.sub.3 n.sub.4") same spacer\$1) and (((silicon adj (oxide or dioxide)) or sio2 or "sio.sub.2") same spacer\$1)))	USPAT; US-PGPUB; JPO	2004/11/06 17:28